FORM PTO-1449/A and B (Modified)	APPLICATION NO.: 09/836,743	ATTY. DOCKET NO.: V0077/7192
INFORMATION DISPLOSURE STATEMENT BY APPLICANT	FILING DATE: April 17, 2001	
STATEMEN LARY APPLICANT	APPLICANT: Liebert et al.	
Sheet 1 3 of	GROUP ART UNIT: Not Yet Assigned 2881	EXAMINER: Not Yet Assigned  K. NG VYEV
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#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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